

Applicant: Kei-Yu Ko
 Serial No.: 08/846,671
 Filing Date: April 30, 1997
 For: UNDOPED SILICON DIOXIDE AS AN ETCH STOP FOR SELECTIVE ETCH OF
 DOPED SILICON DIOXIDE

Att'y DocketNo. 11675.114

70595

JUL 22 1997

INFORMATION DISCLOSURE CITATIONS MADE BY APPLICANTU.S. Patent Documents

<u>Examiner Initial*</u>	<u>Patent Number</u>	<u>Issue Date</u>	<u>Name</u>	<u>Class</u>	<u>Sub Class</u>	<u>Filing Date</u>
OAK A1	5,286,344	2/15/94	Blalock et al.	156	657	6/15/92
A2	5,366,590	11/22/94	Kadomura	156	662	3/17/94
OAK A3	5,423,945	6/13/95	Marks et al.	156	662.1	9/8/92
A4						
A5						

Foreign Patent Documents

<u>Examiner Initial*</u>	<u>Document Number</u>	<u>Publ. Date</u>	<u>Country or Patent Office</u>	<u>Sub Class</u>	<u>Class</u>	<u>Trans-lation</u>
A6						
A7						

Other Documents

(including author (if listed), title, relevant pages, date of publication including at least month and year).

Examiner
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A8

Examiner: George Goudreau Date Considered: 2-2-001
 *EXAMINER: Initial if reference considered, whether or not citation is in conformance
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